

IN THE CLAIMS:

Please cancel claims 2 and 6 without prejudice or disclaimer, and amend claims 1, 5, 7, 13, 19 and 20 as follows:

1. (Currently Amended) A composition for removing residues from the microstructure of an object comprising:
 - carbon dioxide;
 - an additive for removing the residues comprising a fluoride having a formula $NR_1R_2R_3R_4F$, where R_1 , R_2 , R_3 , and R_4 are each independently an alkyl group, and a basic compound including a quaternary ammonium hydroxide; and
 - a co-solvent for dissolving said additive in said CO_2 at a pressurized fluid condition.
- 2 - 4. (Canceled).
5. (Currently Amended) A composition for removing residues from the microstructure of an object comprising:
 - carbon dioxide,
 - a compound having a hydroxyl group,
 - a fluoride having a formula $NR_1R_2R_3R_4F$, where R_1 , R_2 , R_3 , and R_4 are each independently or an alkyl group, and
 - a basic compound including a quaternary ammonium hydroxide.
6. (Canceled).
7. (Original) The composition of claim [[6]] 5 wherein the basic compound is selected from a mixture of the quaternary ammonium hydroxide[[,]] with an alkylamine, an alkanolamine, and a hydroxylamine, ~~and mixtures thereof~~.
8. (Original) The composition of claim 5 further comprising a co-solvent selected from dimethylacetamide, propylene glycol, dimethylsulfoxide, deionized water, acetic acid, and mixtures thereof.

9. (Original) The composition of claim 8 wherein the co-solvent comprises deionized water.
10. (Previously Presented) The composition of claim 8 wherein the co-solvent does not include water.
- 11 - 12. (Canceled).
13. (Currently Amended) The composition of claim 5 wherein the fluoride is selected from ~~ammonium fluoride~~, tetramethylammoniumfluoride, tetraethylammoniumfluoride, tetrabutylammoniumfluoride, tetrapropylammoniumfluoride, choline fluoride, and mixtures thereof.
14. (Original) The composition of claim 5 wherein the compound is selected from ethanol, methanol, n-propanol, isopropanol, n-butanol, iso-butanol, diethyleneglycolmonomethylether, diethyleneglycolmonoethylether, hexafluoroisopropanol, and mixtures thereof.
15. (Canceled)
16. (Previously Presented) The composition of claim 19 wherein the additive is dissolved within the co-solvent.
17. (Canceled)
18. (Previously Presented) The composition of claim 19 wherein the residues are at least one selected from photoresist, UV-hardened resist, X-ray hardened resist, ashed resists, carbon-fluorine containing polymer, plasma etch residues, organic process contaminants, and inorganic process contaminants.
19. (Currently Amended) A composition for removing residues from the microstructure of an object comprising:

carbon dioxide wherein the carbon dioxide is in a pressurized or a supercritical fluid state;

an additive comprising a fluoride having a formula $NR_1R_2R_3R_4F$, where R_1 , R_2 , R_3 , and R_4 are each independently an alkyl group, and mixtures thereof and ~~optionally~~ a basic compound including a quaternary ammonium hydroxide; and

a co-solvent selected from an alcohol, dimethylacetamide, propylene glycol, dimethylsulfoxide, deionized water, acetic acid, acetone, ethanol, propanol, dimethylformamide, N-methyl-2-pyrrolidone, diethylene glycol methyl ether, and mixtures thereof.

20. (Currently Amended) A composition for removing residues from the microstructure of an object comprising:

from 0.001 to 8 weight percent of an additive comprising a fluoride having a formula $NR_1R_2R_3R_4F$, where R_1 , R_2 , R_3 , and R_4 are each independently an alkyl group, and mixtures thereof and ~~optionally~~ a basic compound including a quaternary ammonium hydroxide;

from 1 to 50 weight percent of a co-solvent selected from an alcohol, dimethylacetamide, propylene glycol, dimethylsulfoxide, deionized water, acetic acid, acetone, ethanol, propanol, dimethylformamide, N-methyl-2-pyrrolidone, diethylene glycol methyl ether, and mixtures thereof; and

carbon dioxide.

21. (Previously Presented) The composition of claim 20 wherein the additive further comprises methane.

22. (Previously Presented) The composition of claim 20 wherein the additive further comprises a surfactant having a CF_x group.

23. (Previously Presented) A composition for removing residues from the microstructure of an object comprising:

carbon dioxide;

an additive for removing the residues comprising a fluoride having a formula $\text{NR}_1\text{R}_2\text{R}_3\text{R}_4\text{F}$, where R_1 , R_2 , R_3 , and R_4 are each independently a hydrogen or an alkyl group, and a quaternary ammonium hydroxide; and

a co-solvent for dissolving said additive in said CO_2 at a pressurized fluid condition.